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Rev. 10/95 Patent and Trademark Office		Application Number	10-677,005			
LIST OF PRIOR ART CITED  BY APPLICANT			RT CITED	Filing Date	September 30, 2003	
				First Named Inventor	Jer-shen Maa	
(use as many sheets as necessary)		Group Art Unit	1763			
		Examiner Name	Goudpean			
Sheet	11	of	1	Attorney Docket No.	SLA.0780	

OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	Ţ	
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Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.